

**METHOD OF MAKING NiFeCo-O-N OR NiFeCo-N FILMS  
FOR SHIELDS AND/OR POLES OF A MAGNETIC HEAD**

**ABSTRACT OF THE DISCLOSURE**

5       A specified amount of  $N_2O$  or  $N_2$  is employed in a process gas of a DC magnetron for sputter depositing single or laminated films of NiFeCo-O-N or NiFeCo-N with a high uniaxial anisotropy  $H_K$  after annealing these films along their hard axes. The films can be used for shield layers and/or pole piece layers in a magnetic head.

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